

Layout Decomposition for Triple Patterning Lithography Bei Yu, Kun Yuan*, Boyang Zhang, Duo Ding and David Z. Pan



ECE Dept. University of Texas at Austin, Austin, USA; *Cadence Design Systems, Inc., San Jose, USA

Introduction



What's Layout Decomposition ? Original layout is divided into several masks Decrease pattern density in each exposure Improve resolution and depth of focus (DOF) Lots of works on Double Patterning Lithography (DPL)

Why Triple Patterning Lithography (TPL) ? Delay of next generation lithography (EUV) Original layout is divided into three masks (colors) to triple effective pitch Achieve further feature-size scaling (22nm/16nm)

Speed-Up Techniques

Independent Component Computation Partition the whole problem into several sub-problems

Bridge Computation Further partition the problem by removing bridges



Layout Graph Simplification



Experimental Results – ISCAS-85 & 89 layouts



Normal ILP uses Independent Component Computation Graph Simplification is effective Still maintain the optimality

Runtime Comparison of Normal ILP and Accelerated ILP



Compared with Double Patterning Lithography (DPL), TPL can Resolve some native conflict from DPL Reduce the number of stitches

Previous Works

DPL Layout Decomposition

Iterative Method (remove conflict \rightarrow minimize stitch) Local Optimal Cut based methodologies (e.g. Yang et. al ASPDAC'2010) Minimize conflict and stitch simultaneously ▶ ILP Formulation (e.g. Yuan et. al ISPD'2009) \rightarrow optimal but slow -Heuristic (Xu et. al ISPD'2010) \rightarrow only for planar layout

TPL Layout Decomposition is HARDER Conflict graph is NOT planar Detect conflict is not P, but NP-Complete Hard to use iterative strategy Solution space is much bigger

Optimal Formulation (ILP)





SDP can further speed-up ILP Compared with Accelerated ILP, SDP can save 42% runtime



Problem Formulation

Graphs Construction:

- Given Layout
- 2. Generate Layout Graph (LG) 3. Projection
- 4. Generate Decomposition Graph (DG)

Two sets of edges: ► *CE*: conflict edge ► SE: stitch edge



Problem: TPL Layout Decomposition

Given DG, CE and SE, assign all the nodes in the DG to three masks (colors) to minimize the stitch number and the conflict number

Two Lemmas:

Deciding whether a planar graph is 3-colorable is NP-complete Coloring a 3-colorable graph with 4 colors is NP-complete

Theorem 1: TPL Layout Decomposition problem is NP-Hard

$x_i \in \{0, 1, 2\}$ $\forall i \in V$

 $\forall e_{ii} \in CE$

 $\forall e_{ii} \in SE$

 $rightarrow \sum c_{ij}$ is the number of conflicts, $\sum s_{ij}$ is the number of stitches Motivated by previous works, (1) can be transferred to ILP Represent 3 colors using two 0-1 variables Solving ILP is NP-Hard problem, suffers from runtime penalty

Semidefinite Programming (SDP) Approximation

 $S_{ii} = X_i \oplus X_i$

New representation of colors • Three vectors $(1, 0), (-\frac{1}{2}, \frac{\sqrt{3}}{2})$ and $(-\frac{1}{2}, -\frac{\sqrt{3}}{2})$ same color: $\vec{v_i} \cdot \vec{v_i} = 1$ ► different color: $\vec{v_i} \cdot \vec{v_i} = -1/2$

Vector Programming: $\min \sum_{\alpha \in \mathcal{I}} \frac{2}{3} (\vec{v}_i \cdot \vec{v}_j + \frac{1}{2}) + \frac{2\alpha}{3} \sum_{e_{ij} \in SE} (1 - \vec{v}_i \cdot \vec{v}_j)$ s.t. $\vec{v_i} \in \{(1,0), (-\frac{1}{2}, \frac{\sqrt{3}}{2}), (-\frac{1}{2}, -\frac{\sqrt{3}}{2})\}$

Equal to Mathematical Formulation (1), still NP-Hard

SDP can achieve near optimal results

(1)

(3)

Experimental Results – very dense layouts

Circuit	SE#	CE#	Accelerated ILP			SDP Based		
			st#	cn#	CPU(s)	st#	cn#	CPU(s)
C1	16	247	1	5	5.5	0	6	0.29
C2	38	289	0	15	17.32	0	16	0.77
C3	24	381	0	14	33.41	0	15	0.32
C4	56	437	9	32	203.17	9	32	0.49
avg.	-	-	2.5	16.5	64.9	2.25	17.3	0.468
ratio			1	1	1	0.9	1.05	0.007

SDP can achieve $140 \times$ speed-up

Decomposed Result



Overview of the TPL Decomposition Flow



Three graph based Speed-Ups

Resolve 3-coloring problem: Integer Linear Programming (ILP)

ILP can be replaced by approximation methods: Semidefinite Programming (SDP) Mapping Algorithm

Relax Vector Programming (2) to Semidefinite Programming (SDP)

SDP: min $A \bullet X$ $X_{ii} = 1, \forall i \in V$ $X_{ij} \geq -rac{1}{2}, \quad \forall e_{ij} \in CE$ $X \succeq 0$

SDP (3) can be solved in polynomial time

Mapping Algorithm • Continuous SDP Solutions \Rightarrow Three Vectors Tradeoff between speed and global optimality



╶╬╀╕╝┝╤┫╬╫╪╢╔╕┟┝╝╬╡╠┽┙┫┑┎╶╧║╄╌╝╠┥╢┥╟┊╝╞┥╋╸╉╸╏ ╉╔<u>╬</u>┝┥╵╽╋╬┙╵╹┟┽╼┼┍┹╽_╋┝╝<mark>┟</mark>╗┥╵┫╺┹╵┍┥┍┥┑╧╵┝┥╴┝┱╧╼╶╧╻┙

S1488 decomposed layout Stitch number: 0 Conflict number: 1

Related work

Related work was accepted by ICCAD'2011 (William J. McCalla Best Paper Award Finalist)

Bei Yu et. al - ECE Department - University of Texas at Austin - Austin, USA

E-Mail: {bei, dpan}@cerc.utexas.edu

WWW:http://www.cerc.utexas.edu/utda